

What is claimed is:

1. A method for forming a Re-Cr alloy film, comprising performing an electroplating process using a plating bath which contains an aqueous solution including:
 - a perrhenate ion in a concentration of 0.0001 to less than 2.0 mol/L; and
 - a chromium (III) ion in a concentration of greater than 0.001 to 10.0 mol/L,wherein the molar ratio of the perrhenate ion to the chromium (III) ion in said plating bath is in the range of greater than 0.001 to less than 0.1,
 - wherein said plating bath has a pH of 0 to 8, and a temperature of 10 to 80°C.
2. A method for forming a Re-Cr alloy film, comprising performing an electroplating process using a plating bath which contains an aqueous solution including:
 - a perrhenate ion in a concentration of 0.0001 to less than 2.0 mol/L;
 - a chromium (III) ion in a concentration of greater than 0.001 to 10.0 mol/L; and
 - at least one ion selected from the group consisting of potassium, rubidium, cesium, calcium, strontium and barium ions, in a concentration of 0.001 to 10.0 mol/L,wherein said plating bath has a pH of 0 to 8, and a temperature of 10 to 80°C.
3. The method as defined in claim 1 or 2, wherein said alloy film to be formed has a composition consisting of Re in the range of greater than zero to less than 98% by atomic composition, and the remainder being Cr except inevitable impurities.
4. A method for forming a Re-based film, comprising performing an electroplating process using a plating bath which contains an aqueous solution including:
 - a perrhenate ion in a concentration of 0.001 to 2.0 mol/L; and
 - a chromium (III) ion in a concentration of 0.01 to 10.0 mol/L, wherein the molar ratio of the perrhenate ion to the chromium (III) ion in said plating bath is 0.1 or more,wherein said plating bath has a pH of 0 to 8, and a temperature of 10 to 80°C.
5. The method as defined in claim 4, wherein said film to be formed has a composition consisting of greater than 98% or more, by atomic composition, of Re, with the remainder being Cr and inevitable impurities.

6. The method as defined in either one of claims 1 to 5, wherein said plating bath contains an organic acid in a concentration of 0.1 to 15.0 equivalents to the concentration of all of said metal ions.

7. A method for forming a Re-Cr-Ni alloy film, comprising performing an electroplating process using a plating bath which contains an aqueous solution including:

a perrhenate ion in a concentration of 0.01 to 2.0 mol/L;

a chromium (III) ion in a concentration of greater than 0.8 to 4.0 mol/L; and

a nickel (II) ion in a concentration of 0.0001 to 0.2 mol/L,

wherein said plating bath has a pH of 0 to 8, and a temperature of 10 to 80°C.

8. The method as defined in claim 7, wherein the molar ratio of the chromium (III) ion to the nickel (II) ion in said plating bath is 2 or more.

9. The method as defined in claim 7 or 8, wherein said film to be formed has a composition consisting of Re in the range of 50 to less than 98% by atomic composition, Cr in range of 2 to less than 45% by atomic composition, and the remainder being Ni except inevitable impurities.

10. The method as defined in either one of claims 7 to 9, wherein said plating bath contains an organic acid and/or a boric acid, in a concentration of 0.1 to 5.0 equivalents to the concentration of all of said metal ions.

11. The method as defined in either one of claims 1 to 10, wherein said plating bath contains an ammonium ion in a concentration of 0.0001 to 5.0 mol/L, and/or a boric acid in a concentration of 0.0001 to 5.0 mol/L.

12. The method as defined in either one of claims 1 to 11, wherein said plating bath contains a bromine ion in a concentration of 0.0001 to 5.0 mol/L.

13. The method as defined in either one of claims 1 to 12, wherein said plating bath contains a sulfate ion in a concentration of 0.0001 to 5.0 mol/L, a chloride ion in a concentration of 0.0001 to 5.0 mol/L, a lithium ion in a concentration of 0.0001 to 5.0 mol/L,

a sodium ion in a concentration of 0.0001 to 5.0 mol/L, and/or a potassium ion in a concentration of 0.0001 to 5.0 mol/L.